

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of :
Toshikazu TACHIKAWA et al. :
Serial No. [NEW] : Attn: Application Branch
Filed January 24, 2002 : Attorney Docket No. 2002-0069



NEGATIVE-WORKING PHOTORESIST
COMPOSITION
(Rule 1.53(b) Continuation-in-Part
of Serial No. 09/638,872,
Filed August 15, 2000)

THE COMMISSIONER IS AUTHORIZED
TO CHARGE ANY DEFICIENCY IN THE
FEE FOR THIS PAPER TO DEPOSIT
ACCOUNT NO. 23-0975.

CLAIM OF PRIORITY UNDER 35 USC 119

Assistant Commissioner for Patents,
Washington, DC 20231

Sir:

Applicants in the above-entitled application hereby claim the date of priority under the International Convention of Japanese Patent Application No. 11-234688, filed August 20, 1999, as acknowledged in the Declaration of this application.

A certified copy of said Japanese Patent Application is of record in parent application

Serial No. 09/638,872, filed August 15, 2000.

Respectfully submitted,

Toshikazu TACHIKAWA et al.

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January 24, 2002

English translation of Official Letter
in Taiwanese patent application

Notice of Office Action

Receiver: TOKYO OHKA KOGYO CO., LTD.

Mailed: June 19, 2003

1. Application No.: 089116541
2. Title of the invention: NEGATIVE-WORKING PHOTORESIST
COMPOSITION
3. Applicant: Name: TOKYO OHKA KOGYO CO., LTD.
Address: Japan
4. Attorney:
5. Filing date: August 16, 2000
6. Priority data: 08/20/1999 Japan 11-234688
7. Examiner:
8. Content of decision:
Syllabus: The present invention is rejected.
Ground: Paragraph 2 of Article 20 of the Patent Law.
Reasons:
 - (1) The "negative-working photoresist composition" of the present invention is characterized in that the composition comprises an alkali-soluble resin, a radiation-sensitive acid-generating agent and a crosslinking agent.
 - (2) It is investigated that the crosslinking agent employed in the present invention is a commercial product, and those crosslinking agents from the same series are all conventionally known and used as disclosed in, for example, USP 5928837 and USP 5700625. Accordingly, the claimed content of the present invention employs prior art or knowledge in a way people skilled in the same field may easily accomplish it. The present invention is thus hardly

considered as a creation of highly advanced technical thoughts, and is devoid of inventive steps.

In conclusion, the instant application fails to conform to the statutory patent requirements and therefore a patent should not be granted thereto in accordance with Paragraph 2 of Article 20 of the Patent Law.

經濟部智慧財產局專利核駁審定書

受文者：東京應化工業股份有限公司（代理人：林志剛 先生）

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發文日期：中華民國九十二年六月十九日
發文字號：（九二）智專二（六）01061字

第〇九二二〇六〇七三四〇號

一、申請案號數：〇八九一一六五四一

二、發明名稱：負型光阻組成物

三、申請人：

名稱：東京應化工業股份有限公司

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五、申請日期：八十九年八月十六日

六、優先權項目：

1 1999/08/20 日本11-234688

本 書	發 信 日
2003年6月19日	2003年6月19日
受 信 日	FIPO

專利分類IPC(7)：...G03F 7/038



七、審查人員姓名：劉瑞祥 委員

八、審定內容：

主文：本案應不予專利。

依據：專利法第二十條第二項。

理由：

- (一) 本案所請「負型光阻組成物」特徵為組成物中含有碱可溶性樹脂、光酸生成劑及架橋劑。
- (二) 經查本案所使用之架橋劑為市售商品，且同系列之架橋劑均為習知且習用者，如US 5928837、570625所揭示，故本案所請為由習用技術、知識所顯而易知，且易於完成者，難謂高度技術思想之創作，不具進步性。

據上論結，本案不符法定專利要件，爰依專利法第二十條第二項，審定如主文。

局長
蔡練生

裝

訂

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依照分層負責規定授權單位主管決行
如不服本審定，得於文到之次日起三十日內，備具再審查理由書一式二份及規費新台幣陸仟元
整（專利說明書及圖式合計在五十頁以上者，每五十頁加收新台幣五百元，其不足五十頁者以
五十頁計），向本局申請再審查。